

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Document No. APPM/4180	Serial No. 09/902,518
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT		Applicant Huang et al.	Confirmation No.:
(Use several sheets if necessary)		Filing Date 07/10/2001	Group 150
Examiner Unknown			

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*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
<i>MA</i>	A1	3,510,369	05-05-1970	Ernick et al.	148	187	03-18-1968
	A2	4,028,155	06-07-1977	Jacob	156	643	08-10-1976
	A3	4,262,631	04-21-1981	Kibacki	118	723	10-01-1979
	A4	4,308,089	12-29-1981	Iida et al.	156	643	05-09-1980
	A5	4,420,386	12-13-1983	White	204	192	04-22-1983
	A6	4,532,150	07-30-1985	Endo et al.	427	39	12-22-1983
	A7	4,634,601	01-06-1987	Hamakawa et al.	427	39	03-26-1985
	A8	4,711,698	12-08-1987	Douglas	156	643	07-15-1985
	A9	4,759,947	07-26-1988	Ishihara et al.	427	38	10-07-1985
	A10	4,872,947	10-10-1989	Wang et al.	156	643	10-26-1988
	A11	4,895,734	01-23-1990	Yoshida et al.	427	38	03-30-1988
	A12	4,951,601	08-28-1990	Maydan et al.	118	719	06-23-1989
<i>MA</i>	A13	4,980,196	12-25-1990	Yasuda et al.	427	38	02-14-1990

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<i>MA</i>	B1	DE 19521150 A1	12-14-1995	GERMANY	HO1L	23/522	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B2	DE 19751785A1	05-28-1998	GERMANY	HO1L	21/768	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B3	EP 0776037A2	05-28-1997	EUROPE	HO1L	21/768	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MA</i>	B4	EP 0430303A2	06-05-1991	EUROPE	HO1L	21/285	<input checked="" type="checkbox"/>	<input type="checkbox"/>

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<i>MA</i>	C1	Omar M., "Elementary Solid State Physics: Principles and Applications", pp. 124-125 (1975).
<i>MA</i>	C2	A Darchen, R Drissi-Daoudi, A Irzho, "Electrochemical Investigations of Copper Etching by Cu (NH ₃) ₄ C1 ₂ in Ammoniacal Solutions", Journal of Applied Electrochemistry, 1997, 27 (4)

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<i>ML</i>	A14	4,994,410	02-19-1991	Sun et al.	437	192	02-16-1990
	A15	5,000,113	03-19-1991	Wang et al.	118	723	12-19-1986
	A16	5,000,819	03-19-1991	Pedder et al.	156	643	11-29-1989
	A17	5,011,706	04-30-1991	Tarhay et al.	427	39	04-12-1989
	A19	5,043,299	08-27-1991	Chang et al.	437	192	12-01-1989
	A20	5,086,014	02-04-1992	Miyata et al.	437	103	09-18-1990
	A21	5,121,706	06-16-1992	Nichols et al.	118	719	09-21-1990
	A22	5,232,871	08-03-1993	Ho	437	190	06-03-1992
	A23	5,232,872	08-03-1993	Ohba	437	192	03-05-1992
	A24	5,238,866	08-24-1993	Bolz et al.	437	100	09-11-1991
	A25	5,248,636	09-28-1993	Davis et al.	437	225	06-02-1992
<i>ML</i>	A26	5,266,154	11-30-1993	Tatsumi	156	643	04-27-1992

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<i>ML</i>	B5	EP 0553961A2	08-04-1993	EUROPE	HO1L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B6	EP 0849779A2	06-24-1998	EUROPE	HO1L	21/306	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B7	FR 2712119	05-12-1995	FRANCE	HO1L	21/306	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B8	GB 2283461A	05-10-1995	GREAT BRITAIN	CO4B	41/53	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>ML</i>	B9	GB 2290166A	12-13-1995	GREAT BRITAIN	HO1L	21/3213	<input checked="" type="checkbox"/>	<input type="checkbox"/>

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<i>ML</i>	C3	S. S. Wong, C. G. Sodini, T. W. Ekstedt, H. R. Grinolds, K. H. Jackson, and S. H. Kwan, "Low Pressure Nitrided-Oxide as a Thin Gate Dielectric for MOSFET's," Vol. 130, No. 5, pp. 1139-1144
<i>ML</i>	C4	Takashi Ito, Takao Nozaki, and Hajime Ishikawa, "Direct Thermal Nitridation of Silicon Dioxide Films in Anhydrous Ammonia Gas," J. Electrochem. Soc., Vol. 127, No. 9, pp. 2053-2057

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<i>MA</i>	A27	5,360,491	11-01-1994	Carey et al.	136	256	04-07-1993
	A28	5,401,613	03-28-1995	Brewer et al.	430	323	02-12-1992
	A29	5,409,543	04-25-1995	Panitz et al.	134	2	12-22-1992
	A30	5,423,941	06-13-1995	Komura et al.	156	643.1	11-17-1993
	A31	5,424,246	06-13-1995	Matsuo et al.	437	192	07-30-1993
	A32	5,427,621	06-27-1995	Gupta	134	1	10-29-1993
	A33	5,451,263	09-19-1995	Linn et al.	134	1.1	02-03-1994
	A34	5,458,907	10-17-1995	Ishido	427	96	02-07-1994
	A35	5,465,680	11-14-1995	Loboda	117	84	07-01-1993
	A36	5,468,978	11-21-1995	Dowben	257	258	07-07-1993
<i>MA</i>	A37	5,476,182	12-19-1995	Ishizuka et al.	216	68	09-08-1993

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<i>MA</i>	B10	EP 0520519 A1	12-30-1992	EUROPE	H01J	37/32	X	<input type="checkbox"/>
	B11	EP 0725440 A2	08/07/1996	EUROPE	H01L	23/532	X	
	B12	EP 0416400 A1	03-13-1991	EUROPE	C23C	16/44	X	
	B13	WO 93/17453	09-02-1993	PCT International	H01L	21/306		
<i>MA</i>	B14	2 775 986	09-17-1999	FRANCE	C23F	1/12		X

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<i>MA</i>	C5	Tetsuya Tagawa, Koji Urabe, Makoto Sekine, Yoshiaki Yamada and Takamaro Kikkawa, "Low Contact Resistance Metallization for Gigabit Scale DRAM's Using Fully-Dry Cleaning by Ar/H ₂ ECR Plasma," IEEE Transactions on Electron Devices, Vol. 44, No. 4, April 1997, pp. 588-93.
<i>MA</i>	C6	Yasushi Sawada, Hiroshi Tamaru, Masuhiro Kogoma, Motoaki Kawase, and Kenji Hashimoto, "The Reduction of Copper Oxide Thin Films With Hydrogen Plasma Generated By An Atmospheric-Pressure Glow Discharge," J. Phys. D: Appl. Phys. 29 (1996), pp. 2539-2544.

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<i>ME</i>	A38	5,480,300	01-02 1996	Okoshi et al.	432	241	05/15/1992
	A39	5,527,718	06-18-1996	Seita et al.	437	11	12-28-1994
	A40	5,531,862	07/02/1996	Otsubo et al.	156	643.1	07-19-1994
	A41	5,545,592	08-13-1996	Iacoponi	437	200	02-24-1995
	A42	5,565,084	10-15-1996	Lee et al.	205	646	06-07-1995
	A43	5,572,072	11-05-1996	Lee	257	751	11-16-1994
	A44	5,591,566	01-01-1997	Ogawa	430	325	06-07-1995
	A45	5,607,542	03-04-1997	Wu, et al.	156	643.1	11-01-1994
	A46	5,627,105	05-06-1997	Delfino et al.	438	627	04-08-1993
	A47	5,641,607	06-24-1997	Ogawa et al.	430	272.1	09-28-1995
<i>ME</i>	A48	5,643,834	07-01-1997	Harada, et al.	437	210	05-25-1995

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<i>ME</i>	B15	197 17 698 A1	10-29-1998	DE	H05K	3/26		X
	B16	197 02 124 A1	07-23-1998	DE	B01J	19/08		X
	B17	JP11-16912	01/22/1999	JP (Abstract)	438	115	X	<input type="checkbox"/>
<i>ME</i>	B18	04273442	09-29-1992	JP (Abstract)			X	<input type="checkbox"/>

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<i>ME</i>	C7	Kazuo Kanehiro, et al. "Cleaning of copper or copper alloy for dry coating"; Chemical Abstracts, Vol. 107, No. 26, page 283; 28 December 1987.
	C8	Research Disclosure XP000099373, "Low Temperature Process for Surface Cleaning", No. 309, page 82, 1 January 1990
<i>ME</i>	C9	S. Hymes, et al. "Surface Cleaning of Copper by Thermal and Plasma Treatment in Reducing and Inert Ambients", 1 Vac. Sci. Technol. Vol 16, No. 3 May/June 1998; pages 1107-1109
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<i>MA</i>	A49	5,660,682	08-26-1997	Zhao, et al.	438	715	03-14-1996
<i>MA</i>	A50	5,674,373	10-17-1997	Negrerie, et al.	205	160	07-11-1994
<i>MA</i>	A51	5,658,834	08-19-1997	Dowben	438	478	11-17-1995
<i>MA</i>	A52	5,691,209	11-25-1997	Liberkowski	437	7	10-15-1996
<i>MA</i>	A53	5,710,067	01-20-1998	Foote et al.	437	238	06-07-1995
<i>MA</i>	A54	5,711,987	01-27-1998	Bearinger et al.	427	7	10-04-1996
<i>MA</i>	A55	5,725,938	03-10-1998	Jin, et al.	428	210	08-29-1996
<i>MA</i>	A56	5,726,097	03-10-1998	Yanagida	438	622	07-25-1995
<i>MA</i>	A57	5,730,792	03-24-1998	Camilletti et al.	106	287.14	10-04-1996
<i>MA</i>	A58	5,736,002	04-07-1998	Allen et al.	156	628.1	08-22-1994
<i>MA</i>	A59	5,741,626	04-21-1998	Jain et al.	430	314	04-15-1996

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<i>MA</i>	B19	GB 2319532A	05-27-1998	GREAT BRITAIN	C23C	14/58	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MA</i>	B20	GB 2319533A	05-27-1998	GREAT BRITAIN	C23C	14/58	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MA</i>	B21	JP 05235541	09-10-1993	JP (Abstract)	H05K	3/38	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MA</i>	B22	JP 06097111	04-08-1994	JP (Abstract)	HO1L	21/28	<input checked="" type="checkbox"/>	<input type="checkbox"/>

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<i>MA</i>	C10	Richard Swope, Woo Sik Yoo, Julian Hsieh, Shari Shuchmann, Ferenc Nagy, Harald te Nijenhuis, and David Mordo, "Improvement of Adhesion Properties of Fluorinated Silica Glass Films by Nitrous Oxide Plasma Treatment," J. Electrochem. Soc., Vol. 144, No. 7, July 1997, Pages 2559-2564
<i>MA</i>	C11	S. Takeishi, H. Kudah, R. Shinohara, A. Tsukune, Y. Satoh, H. Miyazawa, H. Harada, and M. Yamada, "Stabilizing Dielectric Constants of Fluorine-Doped SiO ₂ Films by N ₂ O-Plasma Annealing," J. Electrochem. Soc., Vol. 143, No. 1, January 1996, Pages 381-384

Examiner <i>Michael R. Blum</i>	Date Considered <i>9/24/02</i>
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<i>MAL</i>	A60	5,776,235	07-07-1998	Camilletti et al.	106	287.1	10-04-1996
	A61	5,779,807	07-14-1998	Dornfest et al.	134	1.2	10-29-1996
	A62	5,780,163	07-14-1998	Camilletti et al.	428	446	06/05/1996
	A63	5,789,316	08-04-1998	Lu	438	637	03-10-1997
	A64	5,789,776	08-04-1998	Lancaster et al.	257	296	09-18-1996
	A65	5,790,365	08-04-1998	Shel	361	234	07-31-1996
	A66	5,801,098	09-01-1998	Fiordalice et al.	438	653	09-03-1996
	A67	5,817,579	10-06-1998	Ko et al.	438	740	04-09-1997
	A68	5,818,071	10-06-1998	Loboda et al.	257	77	02-02-1995
	A69	5,827,785	10-27-1998	Bhan et al.	438	784	10-24-1996
<i>MAL</i>	A70	5,843,847	12-01-1998	Pu, et al.	438	723	04-29-1996

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<i>MAL</i>	B23	4-72724	06-03-1992	JP				X
	B24	07201738	08-04-1995	JP (Abstract)	H01L	21/205	X	<input type="checkbox"/>
	B25	07021749	08-04-1995	JP (Abstract)	H01L	21/205	X	<input type="checkbox"/>
<i>MAL</i>	B26	61000579	01-06-1986	JP (Abstract)	C23C	16/50	X	<input type="checkbox"/>

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<i>MAL</i>	C12	K. Mikagi, H. Ishikawa, T. Usami, M. Suzuki, K. Inoue, N. Oda, S. Chikaki, I. Sakai and T. Kikkawa, "Barrier Metal Free Copper Damascene Interconnection Technology Using Atmospheric Copper Reflow and Nitrogen Doping in SiOF Film," © 1996 IEEE, IEVM 96, 365-368, Pages 14.5.1-14.5.4
<i>MAL</i>	C13	Ogawa et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K1 Factor", <i>Proceedings of the SPIE. Optical/Laser Microlithography V</i> , vol. 1674, 1992, pages 362-375.

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<i>ML</i>	A71	5,849,135	12-15-1998	Selwyn	156	345	03-12-1996
	A72	5,869,396	02-09-1999	Pan et al.	438	647	07-15-1996
	A73	5,876,891	03-02-1999	Takimoto et al.	430	71	05-26-1995
	A74	5,877,087	03-02-1999	Mosely, et al.	438	656	11-21-1995
	A75	5,899,720	05-04-1999	Mikagi	438	303	12-22-1995
	A76	5,950,083	09-07-1999	Inoue, et al.	438	233	09-25-1995
	A77	5,970,378	10-19-1999	Shue, et al.	438	656	07-23-1997
	A78	6,033,537	03-07-2000	Suguro	204	192.2	12-22-1997
	A79	6,107,192	08-22-2000	Subrahmanyam et al.	438	637	12-30-1997
<i>ML</i>	A80	6,125,859	10-03-2000	Kao et al.	134	1.1	07-11-1997

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							YES	NO
<i>ML</i>	B27	06204191	07-22-1994	JP (Abstract)	H01L	21/302	X	
	B28	62 158 859	07-14-1987	JP			X	
	B29	0 613 178 A2	02-22-1994	EPO	H 01 L	21/90	N/A	
<i>ML</i>	B30	WO 99/33102	07/01/1998	PCT International	H 01 L	21/767	N/A	

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<i>ML</i>	C14	Dijkstra et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", <i>Proceedings of SPIE Optical/Laser Microlithography</i> , Bellingham, SPIE, vol. 1927, pages 275-286.
<i>ML</i>	C15	

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	A82	6,147,009	11-14-2000	Grill et al.	438	780	06-29-1998
	A83	6,159,871	12-12-2000	Loboda et al.	438	786	05-29-1998
	A84	09/082,746		Cohen et al.			05-21-1998
	A85	09/092,811		Yang et al.			06-05-1998
	A86	09/193,920		Rathi et al.			11-17-1998
	A87	09/525,556		Festa et al.			03-15-2000
	A88	09/219,945		Bencher et al.			12-23-1998
	A89	09/165,248		Rathi et al.			10-01-1998
<i>MJC</i>	A90	09/270,039		Huang			03-16-1999
	A91						

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<i>MJC</i>	B31	0 684 671 A1	11-29-1995	EUROPE	H01S	3/025	X	
<i>MJC</i>	B32	0 780 485 A1	06-25-1997	EUROPE	C23C	14/02		X
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant Huang, et al				
(Use several sheets if necessary)				Confirmation No.: 7428				
Examiner UNKNOWN		Filing Date July 10, 2001		Group 2812 <i>2824</i>				
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<i>BL</i>	A1	5,652,166	07/29/1997	Sun, et al.	437	56	01/11/1996	
	A2							
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*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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<i>BL</i>	B1	EP 0070 715 B1	03-18-1987	Europe	G 03 G 5	082	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>BL</i>	B2	GB 2 315 158 A	01-21-1998	UK	H01L 21	336 21	<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>
OTHER ART								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
<i>BL</i>	C1	Australian Patent Office Search Report April 10, m 2002						
	C2							
	C3							
Examiner <i>Michael J. Blum</i>				Date Considered <i>2/16/03</i>				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 608; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/4180	Serial No. 09/902,518
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Huang, et al.	Confirmation No.: 7428
(Use several sheets if necessary)		Filing Date July 10, 2001	Group 2824
Examiner Michael Lebentritt			

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
<i>ML</i>	A1	6,444,568	09/03/2002	Sundararajan et al.	438	627	11/02/2000
	A2						
	A3						
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	A6						
	A7						
	A8						
	A9						
	A10						
	A11						
	A12						
	A13						

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
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	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

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	C1	
	C2	
	C3	

Examiner

Michael Lebentritt

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2/6/03

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